



TECHNISCHE
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IAP-SEMINAR

EINLADUNG

SFB
FOXSI

Termin: **Dienstag, 17.5.2011 um 16:00 Uhr**
Ort: **Technische Universität Wien,
Institut für Angewandte Physik,
Seminarraum 134A, Turm B (gelbe Leitfarbe), 5. OG
1040 Wien, Wiedner Hauptstraße 8-10**

Vortragender: **Prof. Dr. Ing. Guus Rijnders**
Faculty of Science & Technology and MESA+ Institute for
Nanotechnology, University of Twente, Enschede/The Netherlands

Thema: **In-situ monitoring of oxide thin film growth**

Kurzfassung

Complex oxides have attracted great interest since they exhibit a rich spectrum of physical properties such as ferromagnetism, antiferromagnetism, colossal magnetoresistance, ferroelectricity, dielectricity, and superconductivity. Novel heteroepitaxial devices based on these complex oxides, like spin-polarized ferromagnetic tunnel junctions, superconducting devices and piezoelectric devices, have great potential and are currently under investigation in many groups.

The nature of the above-mentioned physical properties in complex oxides is determined by very small characteristic length scales, comparable to the unit cell lattice parameters of complex oxide. Because of these small characteristic length scales, growth control on an atomic level as well as understanding of the different mechanisms affecting the growth mode is essential for the fabrication of epitaxial heterostructures.

Two independent processes, i.e., nucleation and growth of islands, play an important role during vapor-phase epitaxial growth on an atomically flat surface. Here, nucleation causes the formation of surface steps and subsequent growth causes the lateral movement of these steps. Both processes are determined by kinetics, since they take place far from thermodynamic equilibrium. These kinetic processes affect the final surface morphology and are, therefore, extensively studied.

In this contribution, I will demonstrate the applicability of high-pressure RHEED as well as Scanning Force Microscopy (SFM) to monitor the growth of complex oxides during Pulsed Laser Deposition (PLD). Furthermore, I will show recent examples, in which atomically controlled growth enabled new functionalities in complex oxide heterostructures.

*Alle interessierten Kolleginnen und Kollegen sind zu diesem Seminar
(45 min mit anschließender gemeinsamer Diskussion) herzlich eingeladen.*

*U. Diebold e.h.
(Seminar-Chairperson)*

*H. Störi e.h.
(LVA-Leiter)*